

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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Applicant: Chen, et al.

Docket No.: TSM6283131RI

JAN 05 2005

Serial No.: 10/650,886

Art Unit: 1763

Filed: August 28, 2003

Examiner: George A. Goudreau

For: In-Situ Strip Process for Polysilicon Etching in Deep Sub-Micron
TechnologyMail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450Amendment

Dear Sir:

The following amendments and remarks are offered in response to Examiner's Office Action dated October 5, 2004, and are respectfully submitted as a full and complete response to said Action.

In the claims:

Please amend the claims as follows.

20. (New) A method of forming a semiconductor device, the method comprising:
providing a semiconductor substrate with a conductive layer formed thereon;
providing a hard mask layer above said conductive layer;
providing a buffer layer above said hard mask layer;
providing a resist layer above said buffer layer;
patterning said resist layer to form a resist mask that exposes a part of said buffer
layer; and

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FACSIMILE COVER SHEET

To Examiner: George A. Goudreau	Total Pages Sent: 14
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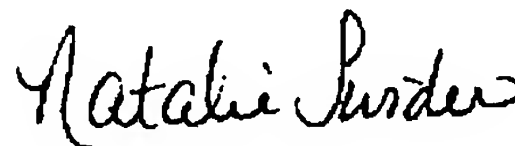
Applicant: Chen, et al. Docket No.: TSM6283131RI
Serial No: 10/650,886 Art Unit: 1763
Date Filed: August 28, 2003
Title: In-Situ Strip Process for Polysilicon Etching in Deep Sub-Micron Technology

CERTIFICATION OF FACSIMILE TRANSMISSION

I hereby certify that the following papers are being transmitted by facsimile to the U.S. Patent and Trademark Office at 703-872-9306 on the date shown above:

- Certification of Facsimile Transmission (1 page)
- Amendment (13 pages)

Respectfully submitted,



Natalie Swider
Legal Assistant

Confirmation Respectfully Requested

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